

<b>Notice of References Cited</b>	Application/Control No. 10/610,481	Applicant(s)/Patent Under Reexamination TUSCHEL ET AL.	
	Examiner L. G. Lauchman	Art Unit 2877	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,473,174	10-2002	Ballast et al.	356/301
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	K. Mizoguchi et al, Micro-Raman characterization of chrystallinity of laser-recrystallized silicon films on SiO2 insulators, Journal of Applied Physics, May 1999, vol. 85, No. 9, pp 6758-6752
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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